

Form PTO-1449
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U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

026827/0154

SERIAL NO.

09/658,023

INFORMATION DISCLOSURE CITATION

FEB 20 2001

(Use several sheets if necessary)

APPLICANT

Boris KOBRIN, et al.

FILING DATE

September 8, 2000

GROUP ART UNIT

~~1758~~ 1763

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>Ans</i>	A9	"Nanometer Sidewall Lithography By Resist Silylation", P. Vettiger, et al., J. Vac. Sci. Technol., Nov./Dec 1989, Vol. 7, No. 6, pages 1756-1759

EXAMINER

DATE CONSIDERED

7/13/02

* **EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.

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OCT 24 2001

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
<i>AW</i>	A1	4,657,845	4/14/87	Frechet et al.	430	326	
	A2	5,858,621	1/12/99	Yu et al.	430	313	
	A3	5,851,733	12/22/98	Sezi et al.	430	314	
	A4	4,377,437	3/22/83	Taylor et al.	156	628	
	A5	4,377,734	3/22/83	Mashiko et al.	219	121	
	A6	4,389,482	6/21/83	Bargon et al.	430	325	
	A7	4,419,809	12/13/83	Riseman et al.	029	570	
	A8	4,445,267	5/1/84	De La Moneda et al.	029	571	
	A9	4,502,914	3/5/85	Trumpp et al.	156	643	
	A10	4,504,574	3/12/85	Meyer et al.	430	331	
	A11	4,552,833	11/12/85	Ito et al.	430	325	
	A12	4,601,778	7/22/86	Robb	156	628	
	A13	4,613,398	9/23/86	Chiong et al.	156	628	
	A14	4,690,729	9/1/87	Douglas	156	643	
	A15	5,599,745	2/4/97	Reinberg	437	195	
	A16	5,792,593	8/11/98	McClure et al.	430	314	
	A17	5,825,609	10/20/98	Andricacos et al.	361	321.4	
	A18	5,665,251	9/9/97	Robertson et al.	216	022	
	A19	5,895,273	4/20/99	Burns et al.	438	719	
	A20	4,358,340	11/9/82	Fu	156	643	
	A21	4,209,349	6/24/80	Ho et al.	148	187	
<i>AW</i>	A22	4,803,181	2/7/89	Buchmann et al.	437	228	

FOREIGN PATENT DOCUMENTS

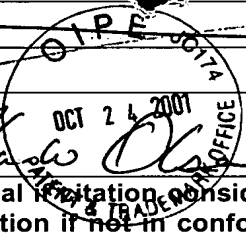
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>AW</i>	B1	Wolf-Dieter Domle, "Chemical amplification of resist lines: The CARL process", Microlithography World, Spring 1999, pp. 2-5.						
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Allen W Ober 7/13/02

09/e58,023

EXAMINER		DATE CONSIDERED
 <i>Mark Ols</i>		7/13/02
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